ABSTRACT OF THE DISCLOSURE

An object of the invention is to improve patterning accuracy while maintaining low cost, high throughput and a high degree of freedom of an optical material in a matrix type display device and a manufacturing method thereof.

In order to achieve the object, surface features, including structural surface features, a desired distribution of water repellency, liquid repellency, hydrophilicity and lyophilicity, or a desired potential distribution are formed by utilizing first bus lines in a passive matrix type display device or utilizing scanning lines, signal lines, common feeder lines, pixel electrodes, an interlayer insulation film, or a light shielding layer in an active matrix type display device. A liquid optical material is selectively coated at predetermined positions by utilizing the surface features.